	Application No.	Applicant(s)
Notice of Allowability	10/605,130	DORIS ET AL.
	Examiner	Art Unit
	David Nhu	2818
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.		
1. This communication is responsive to <u>1/18/05</u> .		
2. The allowed claim(s) is/are <u>1-14 and 21.</u>		
3. The drawings filed on 10 September 2003 are accepted by the Examiner.		
 4.		
(a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached		
1) hereto or 2) to Paper No./Mail Date		
(b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date		
Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).		
7. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.		
Attachment(s) 1. Notice of References Cited (PTO-892) 2. Notice of Draftperson's Patent Drawing Review (PTO-948) 3. Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. Interview Summary Paper No./Mail Dat 7. Examiner's Amenda 8. Examiner's Stateme 9. Other	e

DETAILED ACTIONS

EXAMINER'S AMENDMENT

1. Applicant's election of claims 1-14, 21 is acknowledged. Because Applicant did not distinctly and specifically point out the supposed error in the restriction requirement,

the election has been treated as an election without traverse (MPEP § 818.03(a)). Applicant have the right to file a divisional application covering the subject

The traversal is on the ground(s) that see the election paper. This is not found persuasive because the fields of search for method' and device claims are NOT coextensive and the determinations of patentability of method and device claims are different, that is process limitations and device limitations are given weight differently in determining the patentablitity of the claimed inventions. Also, the strategies for doing text searching of the device claims and method claims are different. Thus, separate searches are required.

The requirement is still deemed proper and is therefore made FINAL.

matter of the non-elected claims 15-20.

An examiner's amendment to the record appears below. Should the change and/or additions be unaceptable to applicant, an amendment may be filed as provided by 37 CFR
 To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

Application/Control Number: 10/605,130 Page 3

Art Unit: 2818

Cancel claims 15-20.

Claim 12 (currently amended), page 8, line 2, "said first layer in said opening" should be -said first **conductive** layer in said opening--

REASONS FOR ALLOWANCE

3. Claims 1-13, 21 are allowed.

4. The following is an examiner's statement of reasons for allowance: None of the references of record teaches or suggests a cited in claims 1, 12: a first conductive layer including one or more materials selected from the group consisting of metal and compounds of metals, said first conductive layer separated from a transistor channel region by a thickness of a gate dielectric; and an overlying conductive silicide layer overlying said first conductive layer (as cited in claim 1); forming a first conductive layer in said opening including at least one material selected from the group consisting of metals and compounds of metals; depositing a layer of silicon on said first conductive layer in said opening; removing said dielectric layer and forming a second metal layer including a silicide-forming metal over said source region and said drain region and said layer of silicon; and annealing said substrate to form a silicide from said sil; icide-forming metal, said silicide contacting said source region and sai drain region and contacting said layer of silicon (as cited in claim 12).

5. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Application/Control Number: 10/605,130 Page 4

Art Unit: 2818

CONCLUSION

6. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure: Kim (6,534,352 B1): Method for Fabricating a MOSFET Device.

7. Any inquiry concerning this communication on earlier communications from the examiner should be directed to David Nhu, (571)272-1792. The examiner can normally be reached on Monday-Friday from 7:30 AM to 5:00 PM.

The examiner's supervisor, David Nelms can be reached on (571)272-1787.

The fax phone number for the organization where this application or proceeding is assigned is (703)872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956

David Nhu

February 16, 2005

DAVID NITION OF THE PRINCIPLE OF THE PRI